

# Jeong Woo Jeon

## List of Publications by Year in descending order

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Version: 2024-02-01

10  
papers

193  
citations

1163117

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1372567

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g-index

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docs citations

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times ranked

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citing authors

#	ARTICLE	IF	CITATIONS
1	Fabrication of a Cu <sup>2+</sup> -Shaped Cation Source Inserted Conductive Bridge Random Access Memory and Its Improved Switching Reliability. <i>Advanced Functional Materials</i> , 2019, 29, 1806278.	14.9	51
2	Time-varying data processing with nonvolatile memristor-based temporal kernel. <i>Nature Communications</i> , 2021, 12, 5727.	12.8	42
3	Atomic layer deposition of chalcogenides for next-generation phase change memory. <i>Journal of Materials Chemistry C</i> , 2021, 9, 3708-3725.	5.5	23
4	Atomic Layer Deposition of Ge <sub>x</sub> Se <sub>1-x</sub> Thin Films for Endurable Ovonic Threshold Selectors with a Low Threshold Voltage. <i>ACS Applied Materials &amp; Interfaces</i> , 2020, 12, 23110-23118.	8.0	19
5	Atomic Layer Deposition of Nanocrystalline-As-Deposited (GeTe) <sub>x</sub> (Sb <sub>2</sub> Te <sub>3</sub> ) <sub>1-x</sub> Films for Endurable Phase Change Memory. <i>Chemistry of Materials</i> , 2019, 31, 8752-8763.	6.7	15
6	Electroforming-Free Bipolar Resistive Switching in GeSe Thin Films with a Ti-Containing Electrode. <i>ACS Applied Materials &amp; Interfaces</i> , 2019, 11, 38910-38920.	8.0	13
7	Developing Precursor Chemistry for Atomic Layer Deposition of High-Density, Conformal GeTe Films for Phase-Change Memory. <i>Chemistry of Materials</i> , 2019, 31, 8663-8672.	6.7	12
8	Kernel Application of the Stacked Crossbar Array Composed of Self-Rectifying Resistive Switching Memory for Convolutional Neural Networks. <i>Advanced Intelligent Systems</i> , 2020, 2, 1900116.	6.1	11
9	Atomic Layer Deposition of SnTe Thin Film Using Sn(N(CH <sub>3</sub> ) <sub>2</sub> ) <sub>4</sub> and Te(Si(CH <sub>3</sub> ) <sub>3</sub> ) <sub>2</sub> with Ammonia Coinjection. <i>Crystal Growth and Design</i> , 2020, 20, 4649-4656.	3.0	5
10	Atomic layer deposition of SnSe thin films using Sn(N(CH <sub>3</sub> ) <sub>2</sub> ) <sub>4</sub> and Se(Si(CH <sub>3</sub> ) <sub>3</sub> ) <sub>2</sub> with NH <sub>3</sub> co-injection. <i>Dalton Transactions</i> , 2022, 51, 594-601.	3.3	2